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(54) VACUUM TREATING DEVICE

(57) Abstract:

PROBLEM TO BE SOLVED: To automatically detect the end point of cleaning treatment for removing material formed and deposited in a vacuum vessel.

SOLUTION: In a vacuum treating device in which the material to be treated is subjected to sputtering or etching in a vacuum vessel 1, it has at least either a pressure detector 5 detecting the pressure in the vacuum vessel 1 and an optical intensity detector 4 detecting the optical intensity in the vacuum vessel 1 and a computing element 6 converting the detected information into electric signals and executing treatment and judgement, and the end point of cleaning treatment for removing material formed and deposited in the vacuum vessel 1 is detected.

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